Supplementary Materials

Photovoltaic arrays as highly efficient system for biomedical and electrochemical surface-enhanced Raman Spectroscopy analysis

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1 Characterization PV surfaces

1.1. Method of PV production.

They are produced by a screen-printing process. It is similar to that used to produce the heating strips on rear and front car windscreens. In the process silver paste is squeezed through a mesh onto the cell surface. In the end it is dried and then fired at a higher temperature to drive off the organic binder in the paste and to allow the silver particles to coalesce. The middle layer p-n junction consists of either mono (hexagonal) or polycrystalline (square) silicon wafer. More than a half of module production is now based on the use of multicrystalline silicon wafers rather than those produced using the Czochralski method. This technique is basing on molten silicon being poured into a container and then allowed to cool. This are doped p-type using boron. In the next step wafers are mechanically and chemically polished to remove any damage from previous wafers creating processes. The surface is then anisotropically etched to texture the surface of the silicon. The main reason to do so is to minimise possible reflection losses and to increase the range of angles at which light rays are refracted into the silicon, what causes enhancement in the optical path length. A p-n junction are produced in the wafers in the process of diffusing phosphorus into the surface of the wafer to convert the surface to a n-type region.

The back plate which is an electrical contact to the rear of the p-type region. It is attached by annealing an aluminium layer deposited over the back of the device. The p+ layer not only minimises the back contact resistance but introduces a "back surface field" to reflect minority carriers back toward the depletion region. This effect is even more enhanced by the *Passivated Emitter and Rear Cell* (PERC) technology. In the PERC technology, the back of the silicon wafer is first covered with a special layer of dielectric (insulator), which is covered with holes cut out by a laser. The metallization layer in the form of aluminum is then applied to the dielectric, so that the silicon wafer contacts the metal only through microscopic holes.

The main task of PERC technology is to increase the efficiency of the cell thanks to the dielectric layer, which reflects every light reaching the bottom layer of the plate without generating the electron back into the cell. Through this reflection, photons basically have a second chance to generate electricity.

1.2. SEM and AFM measurements



A) 1m – type, without silver layer

B) 1 – type, without silver layer



C) 2 – type, without silver layer



D) 3 – type, without silver layer

Fig. S1. SEM images at four magnifications of four testes PV samples named 1m, 1, 2, and 3.





Fig. S2. AFM images at different magnifications of Ag/PV SERS-active platforms sputtered with 8 nm layer of silver via PVD technique.





Fig. S3. Histograms of the size of the silver objects on the surface of the PV based substrates.

Ion etched Si



Fig. S4. (A) AFM and (B) SEM images of ion etched silicon covered with silver layer.

1.3. XPS analysis of Ag/PV SERS platform



A)



B) Sample 1-type without Ag







D) Sample 3-type without Ag



sample 3-type with Ag



Fig. S5. XPS surveys on four SERS substrates ((A) - sample 1), ((B) - sample 1m), ((C) - sample 2), and ((D) - sample 3) coated with 8 nm of Ag layer.

Table S1. Normal Raman and SERS band assignments for *p*-ATP.

Normal Raman/p-ATP	SERS/ <i>p</i> -ATP onto Ag/PV	Assignments
powder	substrate	
1597	1576	$vCC, 8a(a_1)$
	1490	vCC + dCH, 19a (a ₁)
	1435	vCC+δCH, 19b (b ₂)
	1393	δ CH+vCC, 3 (b ₂)
	1311	δCH, 9a (a ₁)
1172	1180	δCH, 9a (a ₁)
	1145	δCH, 9b (b ₂)
1090	1078	γ CC+ γ CCC, 18a, (a ₁)
1007	1007	$\gamma CC + \gamma CCC$, 18a, (a ₁)

Abbreviations: v = stretching, δ , $\gamma =$ bending, $\pi =$ wagging. Letters in parentheses indicate

symmetry.

1.4. Sensitivity



Fig. S6. The SERS spectra of *p*-ATP adsorbed onto "type 1m" SERS surface at different concentration (a) 10^{-6} M and (b) 10^{-9} M in ethanol.



2. Analytical performance of Ag/PV SERS platform

Fig. S7. The SERS spectra of *E.coli* recorded on Ag/PV substrate from randomly distributed points. For all spectra, excitation wavelength was at 785 nm, laser power was 1.5 mW, and acquisition time was only 3 seconds. (B) Microscopic image of E.coli deposited onto SERSactive surface (at magnification 50 X).

 Table S2. Assignment of SERS bands depicted in Fig.7 for *B. subtilis* and Caki-1 (renal cancer cells).

Bacillus subtilis		Caki-1 (renal cancer cells)		
Assignment	Range	Assignment	Range	
C-O-C ring deformation	540-575	Tyr (C-C twist) (protein	652-658	
Guanine, tyrosine	640-675			
Adenine, glycoside	713-740	Trp (protein assignment)	725-730	
Cytosine, uracil	745-790			
Symmetric breathing of		$(H_3C)_3N+(lipid assignment)$		
tryptophan (protein assignment)	752-757	PO ₂ symm (nucleic acid	785	
O-P-O (RNA)	800-815	BNA backbone (nucleic acid	827	
C=C deformation, C-N stretching	930-990	assignment)	027	
Phenylalanine, C-C		Tyr, Pro (protein assignment)	850	
aromatic ring stretching	1000-1010	Structural protein modes of	890	
C-C stretching			020	
(phospholipids	1005 1000	C-C str alpha-nelix, Pro, Val	939	
carbohydrates),C-N	1025-1060	(protein assignment)		
stretching		CH ₃ def (protein assignment)	956	
O-P-O (DNA), C-C or		Phe (protein assignment)	1003	
C-O-C stretching	1080-1105	CH ₂ CH ₃ bending modes of	1030-	
(carbohydrates)		lipids	1032	
=C-O-C= (unsaturated	1130-1145	C-N stretch (protein	1094	

fatty acids in linids)		assignment): CC str chain C-	
C-O ring, aromatic		O str (lipid assignment); PO ₂	
aminoacids in proteins	1150-1185	symm (nucleic acid	
unnouclus in proteins			
Amide III (random),		assignment)	
thymine	1215-1295	C-N str bk (protein	1128
		· · · · · · · · · · · · · · · · · · ·	
Amide III (protein), C-		assignment); Porphyrin (lipid	
H deformation	1315-1325	assignment)	
II deformation		Tyr C-H in plane (protein	1170-
Adenine, guanine, CH		ryr C-11 in plane (protein	11/0-
	1330-1345	assignment); T (nucleic acid	1172
deformation		assignment)	
COO- symmetric			
	1390-1415	$C-C_6H_5$ str in phenylalanine	1212
stretching		tyrosine (protein assignment)	
CH ₂ deformation of		Amida III (hata ahaat)	1245
	1440 1475	Ainide III (beta sneet),	1243
proteins, umbrena	1440-14/5	(protein assignment)	
mode of methoxyl (4)		Amide III (random coil)	1267-
Amide II	1510-1560		1207
	1510 1500	(protein assignment); CH=	1270
Adenine, guanine (ring	1570 1505	CH def (lipid assignment)	
stretching), tryptophan	15/0-1595		
		purine bases of DNA (nucleic	1325
		acid assignment)	
		A C (nuclois said aggignment)	1245
		A,O (nucleic acid assignment)	1545
		Sphingoglycolipids (lipid	1373
		assignment)	
		structural protein modes of	1452
		tumors (protein assignment)	
		A,G (nucleic acid assignment)	1552
			1

Phe, Tyr (protein assignment)	1597- 1600
C≡C str of Tyr and Trp	1616-
(protein assignment)	1618
Amide I (protein assignment);	1657-
C=C str (lipid assignment)	1695

3. Reproducibility and sensitivity of SERS substrates.





Fig. S8. The representative SERS spectra *p*-ATP of concentration 10^{-6} M in ethanol recorded from 40 different spots on the four different SERS surfaces (type 1m, 1, 2, and 3) using mapping mode. The spectra were collected over an area 10 x 20 µm with 1.6 steps µm (40 spectra are shown). Each point in the map was recorded using 1.5 mW of 785 nm excitation with 18 seconds integration times.



Fig. S9. The representative SERS spectra *p*-ATP of concentration 10^{-6} M in ethanol recorded from 40 different spots on the five different SERS surfaces prepared separately. The spectra were collected over an area 10 x 20 µm with 1.6 steps µm (40 spectra are shown). Each point in the map was recorded using 1.5 mW of 785 nm excitation with 18 seconds integration times.